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n 1449 (Modified)

Atty Docket No. NOVLP030/NVLS-000497

Application No.: 10/016,017

Information Disclosure
Statement By Applicant

Applicant: Gopinath et al.

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Filing Date

Group

(Use Several Sheets if Necessary)

December 12, 2001

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U.S. Patent Documents

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Form 1449 (Modified) Application No.: Atty Docket No. 10/016,0170 E NOVLP030/NVLS-000497 Applicant: Information Disclosure Statement By Applicant Gopinath et al. Filing Date Group December 12, 2001 2813 (Use Several Sheets if Necessary) **U.S. Patent Documents** Sub-Filing Examiner Initial No. Patent No. Date Patentee Class class Date Foreign Patent or Published Foreign Patent Application Translation Document Publication Country or Sub-Examiner Initial No. No. Date Patent Office Class class Yes No Other Documents Examiner Initial No. Author, Title, Date, Place (e.g. Journal) of Publication Biberger et al., "High Pressure Processing Chamber for Semiconductor Substrate", Pub. No. US 2002/0046707 A1, Pub. Date: April 25, 2002, Appl. No.: 09/912,844, Filed: July 24, 2001, pp. 1-19.

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